1/7 FIG.1

	O ND FILTER	
		PHYSICAL THICKNESS (nm)
6~	SiO ₂	78
5~	Ti, TiO ₂ , Ti ₂ O ₃ , TiO,TiN	25
4~	SiO ₂	51
3~	Ti, TiO2, Ti2O3, TiO, TiN	28
2~	SiO ₂	59
1~	SUBSTRATE; PET	0.1 (mm)

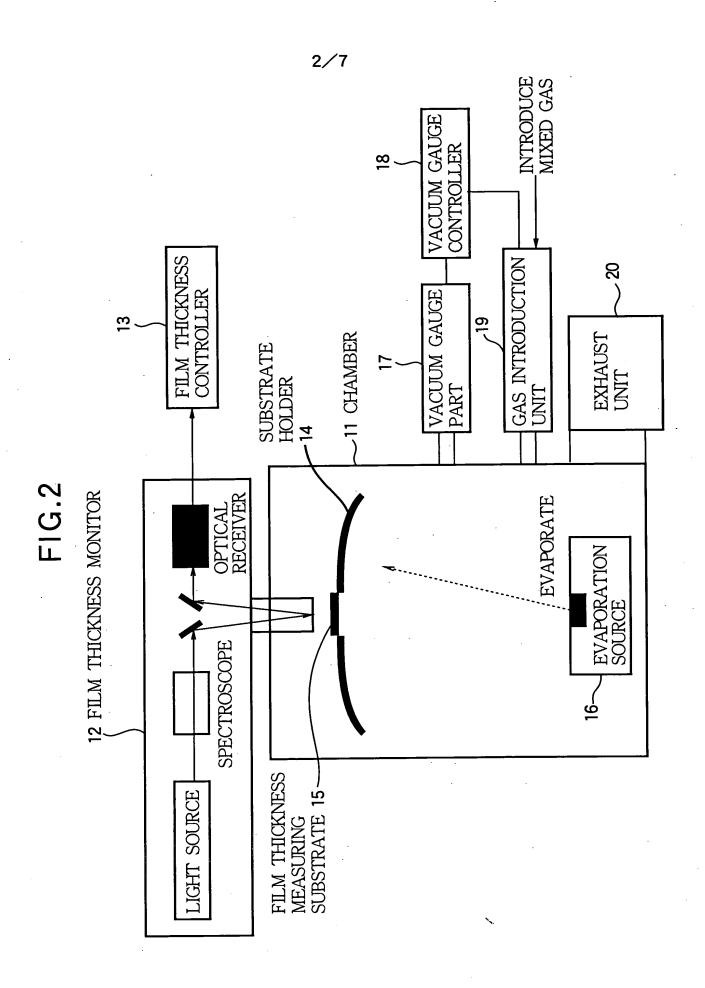


FIG.3

SUBSTRATE TEMPERATORE ULTIMATE VACUUM DEGREE 1×10 ⁻³ P Ti DEPOSITION VACUUM DEGREE 3~4×10 ⁻³ FILM FORMATION FILM FORMATION SiO ₂ INTRODUCED GAS DEPOSITION RATE 0.5~Inm/ OEPOSITION RATE 0.5~Inm/ OEPOSITION CED GAS DEPOSITION RATE 0.5~Inm/ OEPOSITION RATE			THE PLANT OF THE PERSON A PERSON OF THE PERS	100%
ULTIMATE VACUUM DEGREE Ti DEPOSITION VACUUM DEGREE INTRODUCED GAS SiO ₂ INTRODUCED GAS INTRODUCED GAS		SUB	STRATE TEMPERALURE) (0)
Ti DEPOSITION RATE INTRODUCED GAS SiO ₂ INTRODUCED GAS INTRODUCED GAS		ULT	IMATE VACUUM DEGREE	$1 \times 10^{-3} \text{Pa}$
TI DEPOSITION VACUUM DEGREE INTRODUCED GAS SiO ₂ INTRODUCED GAS INTRODUCED GAS			DEPOSITION RATE	0.5~lnm/sec
INTRODUCED GAS DEPOSITION RATE SiO ₂ INTRODUCED GAS		Ħ	DEPOSITION VACUUM DEGREE	$3\sim4\times10^{-3}$ Pa
SiO ₂ INTRODUCED GAS	MATION		INTRODUCED GAS	Air (N2: O2=4:1)
<u> </u>)	(DEPOSITION RATE	0.5~1nm/sec
		SIO2	INTRODUCED GAS	_

4/7 FIG.4

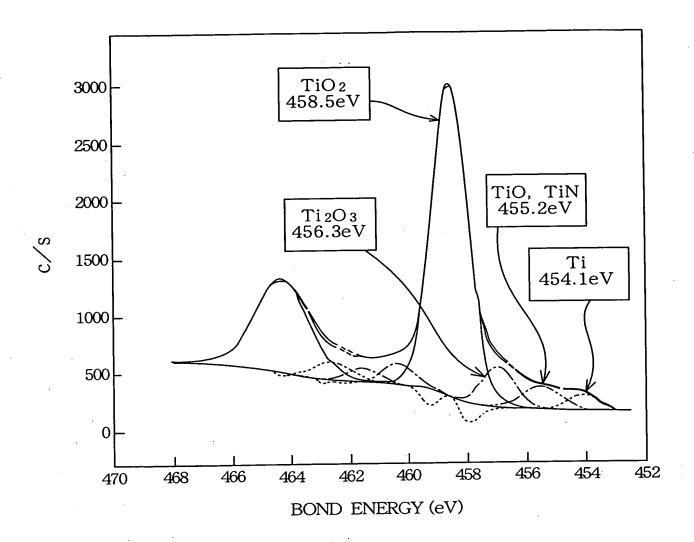


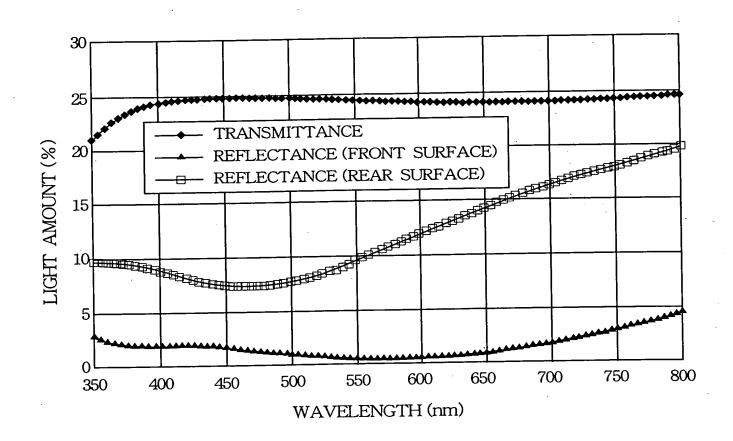
FIG.5

	Ti (METAL)	TiO or TiN	Ti ₂ O ₃	TiO2
ENERGY (eV)	454.1	455.2	456.7	458.5
PROPORTION (%)	5%	5%	10%	80%

5/7 FIG.6

	С	N	0	Ti
PROPORTION(%)	(16.5%)	2.8%	53.8%	27.5%

FIG.7



6/7 FIG.8

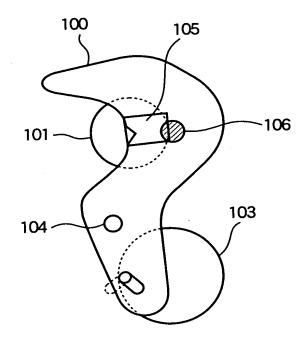


FIG.9

	O ND FILTER	
6~	SiO ₂	
5~	Ti, TiO2, Ti2O3, TiO,TiN	
4~	SiO ₂	
3~	Ti, TiO2, Ti2O3, TiO, TiN	
2~	SiO ₂	
1~	SUBSTRATE; PET	
7~	REFLECTION PREVENTION LAYER	

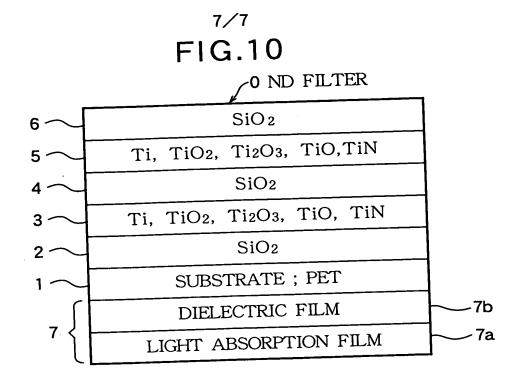


FIG.11 206 DRIVING PORTION 204 APERTURE 201 202 FILTER BLADE BASE PLATE 205 APERTURE 203 COVER PLATE 207 207 -